

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Young Sun Hwang et al.

Serial No.: 10/719,083

Filed:

November 21, 2003

Title:

Methods for Forming Fine

Photoresist Patterns

Group Art Unit:

1765

Examiner: Patricia Ann George

Confirmation:

2261

Attorney Docket No.: 30205/39513

I hereby certify that this paper is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, Virginia 22313-1450, on:

August 2, 2006

Registration No. 28,491 Attorney/for Applicant

PETITION UNDER 37 C.F.R. § 1.136(a)

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, Virginia 22313-1450

Dear Sir:

Applicant, by his attorney, petitions for a one-month extension of time to file a response to the April 10, 2006, official action in the above identified application.

A check is enclosed to cover the required \$120 patent application processing fee under 37 C.F.R. § 1.17(a)(1). Additional fees may be charged to our Deposit Account No. 13-2855.

Respectfully submitted,

MARSHALL, GERSTEIN & BORUN LLP

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August 2, 2006

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